

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Patent Application of

KOBAYASHI, S. Atty. Ref.: 900-471

Appl. No. To be assigned Group:

Filed: August 4, 2003 Examiner:

For: MASK PATTERN AND METHOD FOR FORMING RESIST PATTERN USING
MASK PATTERN THEREOF

* * * * *

August 4, 2003

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Sir:

PRELIMINARY AMENDMENT

In order to place the above-identified application in better condition for examination, please amend the application as follows: